

REMARKS

Claims 12-37, 51-82 and 84-86 are pending in the above-identified application.

Claims 12-37, 51-57, 62-66, 68-82, and 84-86 were allowed. Claim 61 was rejected. With this Amendment, claims 12, 17-29, 52, 54, 61-62, 64-66, 68-69, 72, 82, and 84-86 were amended.

35 U.S.C. § 103 Obviousness Rejection of Claims

Claim 61 was rejected under 35 U.S.C. § 103(a) as being unpatentable over *Yahiro et al.* (U.S. Patent No. 6,204,509) in view of *Mitome et al.* (U.S. Patent No. 5,695,897) further in view of *Fujii et al.* (U.S. Patent No. 5,939,132). Applicants respectfully traverse these rejections.

Claim 61 recites A method of making a mask, which mask has a plurality of pattern formation regions in which mask circuit patterns are formed, and a supporting region in which any mask circuit pattern is not formed, said supporting region being provided for holding said plurality of pattern formation regions while separating said plurality of pattern formation regions from each other, wherein said supporting region has first alignment marks used at time of alignment with said mask for forming said mask circuit patterns thereon, second alignment marks used at a time of alignment with a substrate to be exposed for forming circuit patterns thereon, said method comprising the step of forming all of said first alignment marks and said second alignment marks on said mask at one time, wherein said first alignment marks and said second alignment marks are formed on a mask board by selectively removing said mask board to form holes or grooves in said mask board and burying said holes or grooves with a metal whose atoms have atomic weights heavier than those of atoms of said mask board.

Response to December 15, 2005 Final Office Action

Application No. 10/080,104

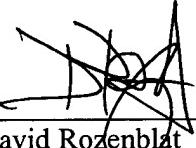
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In this matter, first alignment marks may be used at a time of alignment with "a mask" and second alignment marks may be used at a time of alignment with a "substrate." The *Yahiro et al.* reference does not teach or disclose a first alignment mark used at the time of alignment with "a mask" and a second alignment mark used at the time of alignment with a "substrate."

In view of the foregoing, Applicants submit that the application is in condition for allowance. Notice to that effect is requested.

Respectfully submitted,

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